

Abstract

A substrate support stage and a substrate processing apparatus that improve the cooling performance of a substrate is provided. A substrate
5 support stage includes a base having a lower surface, a first upper surface having a circular shape and located opposite the lower surface, and a second upper surface having an annular shape, located opposite the lower surface and closer to the
10 lower surface than the first upper surface is, and surrounding a periphery of the first upper surface; a first electrostatic chuck disposed over the first upper surface and including a first ceramic member and a first electrostatic electrode disposed in the
15 first ceramic member; and a second electrostatic chuck formed separately from the first electrostatic chuck, disposed over the second upper surface, and including a second ceramic member and a second electrostatic electrode disposed in the second
20 ceramic member.

Fig. 2